

# The role of oxygen in the formation of the Nb<sub>3</sub>Ge film structure with high critical temperatures

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We show that in order to form superconducting Nb<sub>3</sub>Ge films with record high  $T_c$ , oxygen, which stabilizes the A-15 lattice at the film boundary and facilitates the occurrence of seeds of the high-temperature phase, must be present. Total superconductivity was attained at 22.2°K, the critical temperature at  $T_c = 22.5^\circ\text{K}$  and the onset of superconducting transition at 23.2°K.

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Many facts point to the inherent instability of high-temperature superconductors.<sup>1–4</sup> In order to exceed the current record values of critical temperatures  $T_c$  stabilization mechanisms of their high-temperature phases must be investigated. Most interesting from this viewpoint is the compound Nb<sub>3</sub>Ge, the only material today which is fully superconducting at the boiling temperature of hydrogen. A number of recent works note the positive role of oxygen in the formation of Nb<sub>3</sub>Ge with a high  $T_c$ .<sup>5,6</sup> This work is dedicated to the investigation of the stabilizing role of oxygen in the process of formation of Nb<sub>3</sub>Ge films with high, and record, critical temperatures.

*Experiment.* Nb<sub>3</sub>Ge films were prepared by a d.c. cathode sputtering method using a composite target.<sup>7</sup> Sputtering was carried out in an argon atmosphere with various oxygen (and nitrogen) concentrations. From 10 to 13 specimen with different composition were prepared simultaneously.

Sputtering conditions were varied between the following limits: voltage  $V = 480$ – $2300$  V, argon pressure  $P = 0.2$ – $1$  tor. A four-probe method was used to measure film transition into the superconducting state. Temperature was determined with accuracy better than 0.1 K. Liquid hydrogen was used for control purposes. A number of films were subjected to x-ray microanalysis of composition and impurities. Auger spectroscopy was used to study the distribution of components and impurities in the bulk and on the film surface.

*Results.* The effect of oxygen on  $T_c$  of Nb<sub>3</sub>Ge films was investigated over the entire interval of  $P$  and  $V$  (at powers  $\leq 3$  W/cm<sup>2</sup>, limited by Ge melting). High- $T_c$  films were obtained in "hard" ( $P = 0.2$ – $0.4$  tor,  $V \geq 1700$  V) and "soft" ( $P = 0.5$ – $1$  tor,  $V \leq 1700$  V) sputtering regimes (target-to-substrate distance 2 cm). In spite of a certain arbitrariness, such a division is associated with real differences in the specimen properties.

In the "hard" mode, specimen with  $T_c \sim 20$  K were only obtained in argon which contained  $5 \times 10^{-4}\%$  oxygen, for instance in spectrally-pure argon (99.995%,  $2 \times 10^{-3}\%$  nitrogen). In 99.999% pure argon (the principal impurity is nitrogen) or in spectrally-pure argon scrubbed for oxygen to  $2 \times 10^{-5}\%$ ,  $T_c$  was down to 10–15

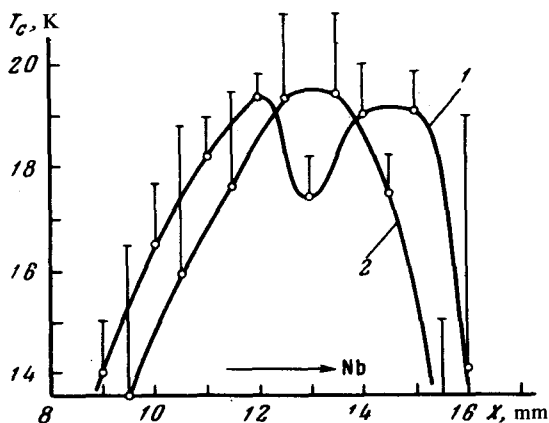


FIG. 1. Dependence of  $T_c$  of  $Nb_3Ge$  films on position on the substrate. This position characterizes specimen composition ( $V = 2000$  V,  $P = 0.3$  tor). Curve 1—for oxygen pressure  $2 \times 10^{-6}$  tor; curve 2— $10^{-5}$  tor. Onset of transition into superconducting state shown for each point.

K. High-temperature highly-reproducible films were formed at increased partial oxygen pressures in the setup to  $(0.4-3.0) \times 10^{-5}$  tor. Experiments involving different  $O_2$  content in argon have clearly established the stabilizing role of oxygen in the formation of  $Nb_3Ge$  films under the influence of various destructive factors: exposure to energetic particles ("hardness" of the regime), nitrogen admixture, deviation of substrate temperature  $T_D$  from optimal, etc.

High- $T_c$  films obtained in "hard" regimes, are characterized by the following: a resistance ratio at 300 K and 25 K  $R_{300}/R_{25} \approx 1.2-1.6$ , presence of "tails" on the transition curves and increased seed size with higher  $O_2$  content in argon. Two maxima were obtained in the dependence of  $T_c$  on composition (Fig. 1) in the case of sputtering in argon with a certain oxygen deficit  $((1-2) \times 10^{-6}$  tor). Moreover, the stoichiometric composition corresponded to a local minimum  $T_c$  and an anomalously-high ratio  $R_{300}/R_{25}$  which attained 4.6.

Films obtained in "soft" regimes were characterized by  $R_{300}/R_{25} = 1.6-3.0$ , well-defined transition curves and a single maximum in the dependence of  $T_c$  on composition. The critical thickness was  $\frac{1}{3}-\frac{1}{4}$  the normal size, becoming smaller as the regime became "softer" (even at a thickness of  $800 \text{ \AA}$   $T_c^{(H)} = 19$  K). Formation of high- $T_c$  films required  $2 \times 10^{-5} \% O_2$  in argon over the entire broad range of  $P$  and  $V$ . The critical temperature increased with improved conditions for purity and moderation of regimes. The maximum purity was attained at  $V = 550-700$  V and  $P = 0.65-0.8$  tor. At oxygen pressures in the setup of  $(0.2-1.0) \times 10^{-6}$  tor in an interval of the highest purity ( $V/P \sim 1$  kV/tor) a region was discovered where samples similar to those obtained in "hard" regimes with oxygen deficit were formed (Fig. 2). In this region oxygen enrichment helped increase the  $T_c$  of specimen. Films with maximum  $T_c$  were obtained at the boundary of the maximum purity region with "softer" regimes. Total superconductivity was attained at 22.2 K with  $T_c = 22.5$  K and  $T_c^{(H)} = 23.2$  K. Significant dependence of  $T_c$  on the film deposition rate was not observed. Specimens with  $T_c > 21$  K were obtained in the rate interval  $0.5-6 \text{ \AA}/\text{sec}$ . The optical  $T_D = 825 \pm 20^\circ \text{C}$ . The oxygen content in the films was  $\leq 2\%$  (less in "soft" regimes), and nitrogen and other impurities  $< 1\%$  (even at  $2 \times 10^{-3} \%$  nitrogen in argon). The

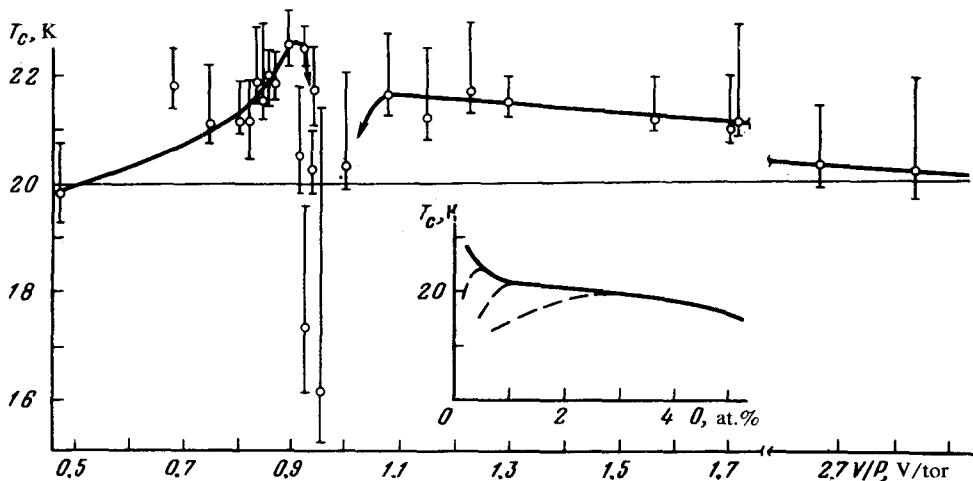


FIG. 2. Dependence of  $T_c$  on  $V/P$  for "soft" regimes. Partial oxygen pressure outside the chamber— $(0.2-1) \times 10^{-6}$  tor. Breaks indicate onset and end of transition. The dependence of  $T_c$  on oxygen content in films is shown qualitatively in the inset. Dotted lines show effect of disruptive factors.

oxygen content at the surface  $\sim 1$  atom per cell, with the thickness of the oxygen-rich layer increasing with enhancement of regime "hardness" and film thickness.

*Discussion.* A more stable  $\sigma$ -phase interferes with the formation of the A-15 phase in  $\text{Nb}_3\text{Ge}$  films near stoichiometry.<sup>8</sup> Having penetrated the lattice, oxygen increases its constant, reduces tetragonal stress and stabilizes it although reducing  $T_c$ . It is important to stabilize both the A-15 phase seeds in the early layers of precipitated film<sup>9</sup> and its surface (protecting it at the same time from energetic particles).

The presence of oxygen at a depth in a film with A-15 lattice is unfavorable energy-wise; oxygen is forced out at the grain boundary and onto the surface (this resembles zone cleaning), i.e., oxygen here basically plays the role of a catalyst. In the process of film growth the Nb and Ge atoms "open up:" in the oxygen-rich surface layer lattice formation also occurs in the lower part of this layer. Both oxygen deficit (absence of stabilization) and an excess of it (partial entrapment inside a film) lower the  $T_c$  (inset in Fig. 2).

The substrate temperature should guarantee a reasonable atomic diffusion rate but hinder the intensive growth of the  $\sigma$ -phase (experiment yields  $650 \text{ C} \leq T_D \leq 900 \text{ }^\circ\text{C}$ ). The model also explains other results. The destabilizing factors require an increased quantity of oxygen to achieve high  $T_c$ ; this leads to distended transitions for which the thickness of an "oxide" layer on the grains exceeds the coherence length. An increase in the oxygen content of films with a substantial  $\text{O}_2$  deficit in argon was observed. The lowering of the coefficient of attachment of oxygen to a film growing under optimal conditions, is associated with the presence of a thin surface layer heavily enriched with oxygen. Sorption of oxygen increases under the conditions of its deficit due to defective lattice structure.

A stabilizing role is also played by some deviation of composition from stoichio-

metric (Fig. 1). For a fixed stoichiometry and oxygen insufficiency a sharp increase in the number of antistructural defects disturbs the intactness of chains as it lowers  $T_c$ . The averaged Heller radii of elements that are in nonequivalent A-15 lattice points, converge somewhat and a stability is attained that preserves the type of lattice while the ratio  $R_{300}/R_{25}$  increases sharply.

*Conclusion.* Oxygen, evidently, is not the unique admixture that is capable of stabilizing the A-15 lattice.<sup>6,10</sup> The effectiveness of oxygen in increasing the  $T_c$  is associated with its displacement to the film surface. The stabilizing effect of admixtures may be used to produce new superconducting compounds. The critical temperature may also be increased in  $Nb_3Ge$  provided purity with respect to oxygen is improved and, concurrently, destabilizing effects are minimized.

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